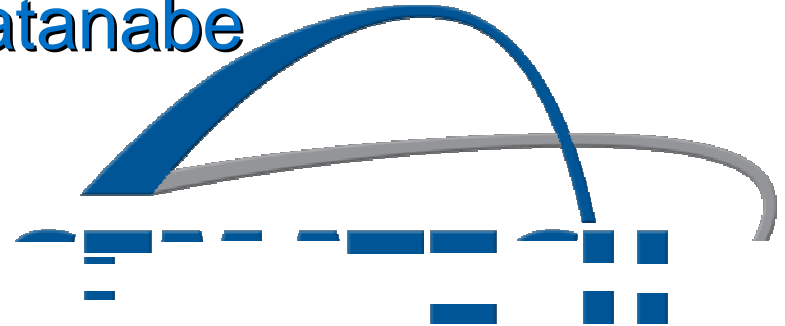


EUV Source Workshop

**San Jose Convention Center, Room J1-J4
8 AM - 8 PM, February 27, 2005, San Jose, CA**

Organization Committee

**Vivek Bakshi (Chair), Vadim Banine, Fred Bijkerk,
Akira Endo, Igor Fomenkov, Kazua Ota,
Joseph Pankert, Uwe Stamm, Koichi Toyoda,
Yutaka Watanabe**



Public Meeting Notice

- This meeting is classified as an “Open Conference” per the U.S. Export Administration Regulations.
- Confidential or Proprietary information may NOT be disclosed.
- All meeting attendees are permitted to take notes or otherwise make a personal record of these proceedings.
- Presentations may be available to the public, including posting on the SEMATECH public website: www.SEMATECH.org

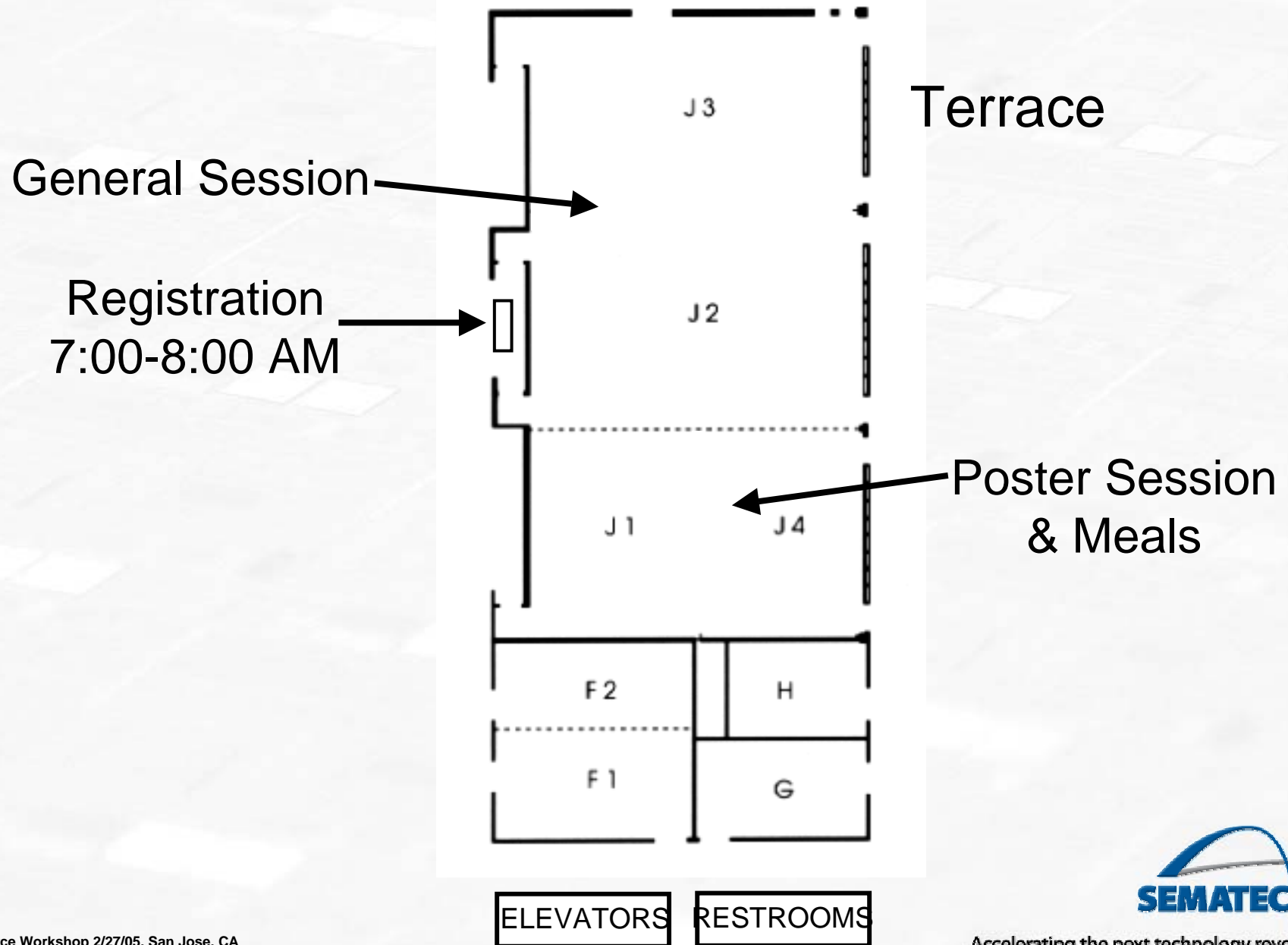


Important Information

- Please remember to wear your badge at all times
- Restrooms are located outside, to your left (look for the signs)
- Breakfast and lunch are next door in J1-J4
- Poster Session is next door in J1-J4 beginning at 5:00 pm
- Please place all pagers and/or cell phones on vibrate only
- For any speaker questions – see Mario Gonzales at the projection table



EUV Source Workshop Meeting Rooms



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
08:00AM	Welcome & Introduction	Vivek Bakshi
	SESSION I: Supplier Updates Session Chair: Kazuya Ota	
08:05AM	<u>Source Status Requirements Update</u>	Yutaka Watanabe
	Supplier Updates Presentations	
08:15AM	<u>Cymer</u>	Igor Fomenkov
08:30AM	<u>EUVA</u>	Akira Endo
08:45AM	<u>EXULITE</u>	Magali Davenet
09:00AM	<u>Philips Extreme</u>	Joseph Pankert
	Session Chair: Akira Endo	
09:15AM	<u>PLEX LLC</u>	Malcolm McGeoch
09:30AM	BREAK	
09:45AM	<u>PowerLase</u>	Samir Ellwi
10:00AM	<u>Xtreme technologies</u>	Uwe Stamm



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
	SESSION II: Sn Based EUV Sources Presentations Session Chair: Robert Bristol	
10:15AM	<u>Sn Plasma Measurements and Fundamental Data</u>	Konstantin Koshelev (Presented by Leonid Shmaenok)
10:30AM	<u>Sn Delivery Systems and Metrology</u>	Guenther Derra
10:45AM	<u>Sn Delivery Systems in EUVA</u>	Yusuke Teramoto
10:50AM	<u>Low Debris Sn Discharge Source</u>	K-Ngo Leung
10:55AM	<u>Sn Debris Mitigation - ANL</u>	Ahmed Hassanein
11:15AM	<u>Sn Debris Mitigation - UIUC</u>	Brian Jurczyk
11:25AM	<u>Sn Debris Mitigation - UCF</u>	Martin Richardson



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
	SESSION III: EUV Resist Performance Panel Discussion Co-Chairs: Vivek Bakshi & Bryan Rice	
	<u>Panel Discussion Guidelines</u>	Vivek Bakshi
		PANELISTS
11:35AM	<u>EUV Resist Performance Trade-Offs</u> (presentation)	Kim Dean & Robert Brainard
11:45AM	Stepper Manufacturer's Perspective on the Present Status of Resist Performance and its Effect on EUV Source Requirements	<u>Hajime Kanazawa, Canon</u> <u>Kazuya Ota, Nikon</u> Hans Meiling, ASML
12:15 PM	LUNCH	



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
	<p>SESSION IV: Collectors for Sn Based Sn Sources</p> <p>Panel Discussion</p> <p>Co-Chairs: Uwe Stamm & Igor Fomenkov</p>	
		<i>PANELISTS</i>
1:15PM	What are the technical limits of tin debris mitigation in DPP EUV sources?	Ahmed Hassanein
	What are the technical limits of tin debris mitigation in LPP EUV sources?	<u>Martin Richardson</u>
	Please provide material's perspective on designing collector for Sn based on EUV sources: UIUC	<u>Brian Jurczyk</u>
	Please provide user's perspective on designing collector for Sn based on EUV sources: Intel	Robert Bristol
	Please provide manufacturer's perspective on designing collector for Sn based on EUV sources: Media-Lario	<u>Giovanni Nocerino</u>
	Audience Feedback	All



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
	SESSION V: EUV Source Metrology Presentations Session Chair: Yutaka Watanabe	
2:00PM	<u>Intermediate Focus Metrology: Development Results</u>	Thomas Missalla
	<u>Intermediate Focus Metrology: Development Results</u>	Leonid Shmaenok
	<u>EUV Source Metrology Calibration</u>	Steve Grantham
	<u>EUV Source & Stepper Interface Requirements</u>	David Brandt
3:00PM	BREAK	



EUV Source Workshop Agenda

TIME	DESCRIPTION	PRESENTER
	<p>SESSION VI: Cost of Ownership Panel Discussion Co-Chairs: Joseph Pankert & Hakaru Mizoguchi</p>	
3:20PM	<u>SEMATECH's COO Model</u>	Phil Seidel
		<i>Panelists</i>
	Supplier's perspective on Cost of Ownership of EUV Sources	<u>Samir Ellwi, PowerLase</u> <u>Uwe Stamm, Xtreme tech.</u> <u>Masaki Yoshioka, EUVA</u>
	Stepper Manufacturer's perspective on Cost of Ownership	<u>Yutaka Watanabe, Canon</u> <u>Hans Meiling, ASML</u> <u>Kazuya Ota, Nikon</u>
	Audience Feedback	
4:30PM	<u>Technology Status and Workshop Summary</u>	Vivek Bakshi
	<p>POSTER SESSION / RECEPTION 5:00-8:00 PM</p>	



EUV Source Workshop Agenda

Poster Session and Reception 5- 8 PM

TIME	DESCRIPTION	
	POSTER SESSION / RECEPTION	
5:00 PM – 8:00 PM	Modeling and Fundamental Data	
	LPP based EUV Sources	
	DPP based EUV Sources	
	EUV Source Metrology	

